L Number	Hits	Search Text	DB	Time stamp
2	4486	(250/310,311,309,492.22).CCLs.	USPAT; US-PGPUB; EPO; JPO;	2003/11/17 13:10
3	43356	(SEM or (scanning adj electron adj microscope))	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/17 13:11
4	30513	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/17 14:07
5	11020	(((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 13:12
6	200	<pre>((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/17 13:14
7	37	<pre>microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:15
8	18	<pre>(pattern near width)) ((((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:15
9	0	<pre>(pattern near width))) and calculat\$5 ((((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:16
10	29	<pre>(pattern near width))) and diminsion\$4 ((((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17
11	29	(pattern near width))) and characteristic (((((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or (pattern near width)) and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:18
12	7	characteristic) and pattern (((((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and characteristic) and pattern) and model	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:19

		(0000 (00 (00
13	5	<pre>((((((((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and characteristic) and pattern) and model)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17
14	1909	and (correct\$4 with exposure) ((observ\$6 or monitor\$4) near4 process\$4) and ((critical\$4 or characteristic) near4 dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 14:09
15	316	(((observ\$6 or monitor\$4) near4 process\$4) and ((critical\$4 or characteristic) near4 dimension\$4)) and ((SEM or (scanning adj electron adj microscope)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 14:10
16	119	<pre>((((observ\$6 or monitor\$4) near4 process\$4) and ((critical\$4 or characteristic) near4 dimension\$4)) and ((SEM or (scanning adj electron adj microscope)))) and (imag\$4 with (resist or photoresist))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:11
17	17	"117" and ((edge or pattern) near4 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17
18	6	("117" and ((edge or pattern) near4 width)) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 14:13
19	5	(("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17
21	4	(((("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4) and pattern\$4) and calculat\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 14:16
22	1	<pre>((((("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4) and pattern\$4) and calculat\$5) and (ion or electron or charged-particle or (charged adj particle))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 14:16
20	5		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17
24	1873	(process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/17 14:37
25	807	((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:38
26	198	(((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:39

1 2 7	720	///mmagagged with manifered 1 and /grad	HCDAT -	2003/11/17
27	139	((((process\$4 with monitor\$4) and (SEM or	USPAT;	14:40
	<u>'</u>	(scanning adj electron adj microscop\$1)))	US-PGPUB;	14:40
		and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and	EPO; JPO; DERWENT;	
		correct\$4	IBM TDB	ļ
28	136		USPAT;	2003/11/17
20	130	or (scanning adj electron adj	US-PGPUB;	14:41
		microscop\$1))) and exposure) and	EPO; JPO;	1 1 1 1 1 1
		((critical\$4 or characteristic\$4) near	DERWENT;	
		dimension\$4)) and correct\$4) and	IBM TDB	[
		((charged adj particle) or electron)	111_111	
29	43	((((((process\$4 with monitor\$4) and (SEM	USPAT;	2003/11/17
23		or (scanning adj electron adj	US-PGPUB;	14:42
		microscop\$1))) and exposure) and	EPO; JPO;	
		((critical\$4 or characteristic\$4) near	DERWENT;	
		dimension\$4)) and correct\$4) and	IBM TDB]
	'	((charged adj particle) or electron)) and	~	
		((pattern or edge) near width)		1
30	42		USPAT;	2003/11/17
		or (scanning adj electron adj	US-PGPUB;	14:43
		microscop\$1))) and exposure) and	EPO; JPO;	1
	'	((critical\$4 or characteristic\$4) near	DERWENT;	
		dimension\$4)) and correct\$4) and	IBM_TDB	
		((charged adj particle) or electron)) and	_	
	·	((pattern or edge) near width)) and		
	'	(calculat\$5 or comput\$4)		
31	41	(((((((process\$4 with monitor\$4) and	USPAT;	2003/11/17
		(SEM or (scanning adj electron adj	US-PGPUB;	14:44
		microscop\$1))) and exposure) and	EPO; JPO;	i i
1	'	((critical\$4 or characteristic\$4) near	DERWENT;	
		dimension\$4)) and correct\$4) and	IBM_TDB	}
		((charged adj particle) or electron)) and		ļ
[((pattern or edge) near width)) and		
	ا م	(calculat\$5 or comput\$4)) and focus\$4	TICDAM.	2002/11/27
32	41	1	USPAT;	2003/11/17 14:44
		(SEM or (scanning adj electron adj microscop\$1))) and exposure) and	US-PGPUB;	Tataa
		microscop\$1/// and exposure/ and ((critical\$4 or characteristic\$4) near	EPO; JPO; DERWENT;	(
		((Cffffed134 of characteristic34) hear dimension\$4)) and correct\$4) and	IBM TDB	
		((charged adj particle) or electron)) and	121125]
1		((pattern or edge) near width)) and		1
		(calculat\$5 or comput\$4)) and focus\$4)		
Į		and (model\$4 or referenc\$4)		
33	21	(((((((((process\$4 with monitor\$4) and	USPAT;	2003/11/17
	21	(SEM or (scanning adj electron adj	US-PGPUB;	14:45
		microscop\$1))) and exposure) and	EPO; JPO;	
		((critical\$4 or characteristic\$4) near	DERWENT;	
		dimension\$4)) and correct\$4) and	IBM TDB	
		((charged adj particle) or electron)) and	_	1
		((pattern or edge) near width)) and		1
į		(calculat\$5 or comput\$4)) and focus\$4)		
į		and (model\$4 or referenc\$4)) and		
	i	(correct\$4 with exposure)		
34	15		USPAT;	2003/11/17
1		(SEM or (scanning adj electron adj	US-PGPUB;	14:45
		microscop\$1))) and exposure) and	EPO; JPO;	
		((critical\$4 or characteristic\$4) near	DERWENT;	[
		dimension\$4)) and correct\$4) and	IBM_TDB]
		((charged adj particle) or electron)) and		1
		((pattern or edge) near width)) and		1
1		(calculat\$5 or comput\$4)) and focus\$4)		
		and (model\$4 or referenc\$4)) and		
		(correct\$4 with exposure)) and (monitor\$4		1
		near2 process\$4)		

35	9	(((((((((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)) and (correct\$4 with exposure)) and (monitor\$4 near2 process\$4)) and lithograph\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:53
36	2	(((((((((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)) and (correct\$4 with exposure)) and (monitor\$4 near2 process\$4)) and lithograph\$4) and ((250/310,311,309,492.22).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:53